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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/663,714	09/17/2003	Daijiro Inoue	57810-076	2234
7590 11/23/2007 McDERMOTT, WILL & EMERY 600 13th Street, N.W.			EXAMINER	
			SEFER, AHMED N	
Washington, De	ngton, DC 20005-3096		ART UNIT	PAPER NUMBER
			2826	
			MAIL DATE	DELIVERY MODE
			11/23/2007	PAPER

Please find below and/or attached an Office communication concerning this application or proceeding.

The time period for reply, if any, is set in the attached communication.

. •	Application No.	Applicant(s)				
••						
Office Action Summary	10/663,714	INOUE ET AL.				
^	Examiner	Art Unit				
The MAILING DATE of this communication a	A. Sefer	2826				
Period for Reply	appears on the cover sheet w	nui lue correspondence address				
A SHORTENED STATUTORY PERIOD FOR REF WHICHEVER IS LONGER, FROM THE MAILING - Extensions of time may be available under the provisions of 37 CFR after SIX (6) MONTHS from the mailing date of this communication If NO period for reply is specified above, the maximum statutory peri - Failure to reply within the set or extended period for reply will, by sta Any reply received by the Office later than three months after the ma earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUN 1.136(a). In no event, however, may a od will apply and will expire SIX (6) MO tute, cause the application to become A	ICATION. reply be timely filed NTHS from the mailing date of this communication. BANDONED (35 U.S.C. § 133).				
Status						
1) Responsive to communication(s) filed on 31	August 2007.					
2a) This action is FINAL . 2b) ⊠ T	This action is FINAL . 2b)⊠ This action is non-final.					
·— ··	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is					
closed in accordance with the practice unde	r <i>Ex par</i> te <i>Quayle</i> , 1935 C.l	D. 11, 453 O.G. 213.				
Disposition of Claims						
4) ⊠ Claim(s) 1-4,6-10,12 and 14-29 is/are pendid 4a) Of the above claim(s) 8,10,17-22,24 and 5) ☐ Claim(s) is/are allowed. 6) ⊠ Claim(s) 1-4,6,7,9,12,14-16,23 and 26-29 is 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and	<u>/ 25</u> is/are withdrawn from c /are rejected.	onsideration.				
Application Papers						
9) The specification is objected to by the Exam 10) The drawing(s) filed on is/are: a) a Applicant may not request that any objection to t	ccepted or b) objected to					
Replacement drawing sheet(s) including the corr	ection is required if the drawing	g(s) is objected to. See 37 CFR 1.121(d).				
Priority under 35 U.S.C. § 119		·				
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documed 2. Certified copies of the priority documed 3. Copies of the certified copies of the papplication from the International Buret * See the attached detailed Office action for a line in the internation of the certified copies of the papplication from the International Buret * See the attached detailed Office action for a line in the internation of the certified copies of the papplication from the International Buret * See the attached detailed Office action for a line in the internation of the certified copies of the priority documents and the certified copies of the papple certified copies of the certified copies of the papple certified copies of the papple certified copies of the certified copies of the certified copies of the certified copies of the papple certified copies of the certifie	ents have been received. ents have been received in a riority documents have been eau (PCT Rule 17.2(a)).	Application No n received in this National Stage				
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Attachment(s)						
1) Notice of References Cited (PTO-892) 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO/SB/08) Paper No(s)/Mail Date	Paper No	Summary (PTO-413) (s)/Mail Date Informal Patent Application 				

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DETAILED ACTION

Response to Arguments

1. Applicant's arguments with respect to claims 1, 26 and 27 have been considered but are most in view of the new ground(s) of rejection.

Claim Rejections - 35 USC § 112

- 2. The following is a quotation of the first paragraph of 35 U.S.C. 112:
 - The specification shall contain a written description of the invention, and of the manner and process of making and using it, in such full, clear, concise, and exact terms as to enable any person skilled in the art to which it pertains, or with which it is most nearly connected, to make and use the same and shall set forth the best mode contemplated by the inventor of carrying out his invention.
- 3. Claims 1, 26 and 27 are rejected under 35 U.S.C. 112, first paragraph, as failing to comply with the written description requirement. The claim(s) contains subject matter which was not described in the specification in such a way as to reasonably convey to one skilled in the relevant art that the inventor(s), at the time the application was filed, had possession of the claimed invention. The application as originally filed does not specifically support the claim limitation, "without another second conductivity type layer having a thickness of less than 0.1 um."

Claim Rejections - 35 USC § 102

4. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

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- (b) The invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 5. Claim 26 is rejected under 35 U.S.C. 102(b) as being anticipated by Ito et al. ("Ito") JP 11-145518.

Ito discloses in fig. 1 a nitride-based semiconductor light-emitting device comprising: a first conductivity type first nitride-based semiconductor layer 3 formed on a substrate 1; an active layer 4 formed on said first conductivity type first nitride-based semiconductor layer; a second conductivity type second nitride-based semiconductor layer 5, having a single layer structure with a thickness of at least 0.1 um (par. 14 of machine translated document) formed on said active layer; an undoes contact layer 6 formed directly on said second nitride-based semiconductor layer without another second conductivity type layer having a thickness of less than 0.1 um intervening therebetween; and an electrode 7 formed directly on said undoped contact layer, wherein said undoped contact layer has a thickness within the recited range (par. 10 of machine translated document).

Claim Rejections - 35 USC § 103

- 6. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 7. Claims 1, 2 and 4 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ito in view Kamimura et al. ("Kamimura") JP 9-232680.

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Ito discloses in fig. 1 a nitride-based semiconductor light-emitting device comprising: a first conductivity type first nitride-based semiconductor layer 3 formed on a substrate 1; an active layer 4 formed on said first conductivity type first nitride-based semiconductor layer; a second conductivity type second nitride-based semiconductor layer 5, having a single layer structure with a thickness of at least 0.1 um (par. 14 of machine translated document); an undoped contact layer 6 formed directly on said second nitride-based semiconductor layer without another second conductivity type layer having a thickness of less than 0.1 um intervening therebetween; and an electrode 7 formed directly on said undoped contact layer, wherein said undoped contact layer has a thickness within the recited range (par. 10 of machine translated document), and the undoped contact layer does not include Al, but does not disclose undoped optical guide layer.

Kamimura discloses in fig. 1 a nitride-based semiconductor light-emitting device comprising a first conductivity type first nitride-based semiconductor layer 3 formed on a substrate; an active layer 5; a first undoped optical guide layer 6 formed on said active layer; a second conductivity type second nitride-based semiconductor layer 7, having a single layer structure formed on said first undoped optical guide layer.

Therefore, in view of Kamimura's teachings, one having an ordinary skill in the art at the time the invention was made would be motivated to modify Ito by incorporating an undoped optical guide layer. The motivation would be to prevent diffusion of dopants into the active layer. Therefore, it would have been obvious to combine Ito and Kamimura so as to yield the device of claim 1.

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Re claim 2, Ito discloses the undoped contact layer (Co) having a band gap smaller than the band gap of said second nitride-based semiconductor layer (GaN).

Re claim 4, Ito discloses a first conductivity type first nitride-based semiconductor layer being an n-type first nitride-based semiconductor layer, and said second conductivity type second nitride-based semiconductor layer being a p-type second nitride-based semiconductor layer.

8. Claims 27 and 28 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ito in view Kamimura.

Ito discloses in fig. 1 a nitride-based semiconductor light-emitting device comprising: a first conductivity type first nitride-based semiconductor layer 3 formed on a substrate; an active layer 4 formed on said first conductivity type first nitride-based semiconductor layer; a second conductivity type second nitride-based semiconductor layer 5, having a single layer structure with a thickness of at least 0.1 um (par. 14 of machine translated document); an undoped contact layer 6 formed directly on said second nitride-based semiconductor layer without another second conductivity type layer having a thickness of less than 0.1 um intervening therebetween; and an electrode 7 formed directly on said undoped contact layer, wherein said undoped contact layer has a thickness within the recited range (par. 10 of machine translated document), but does not disclose undoped optical guide layer.

Kamimura discloses in fig. 1 a nitride-based semiconductor light-emitting device comprising a first conductivity type first nitride-based semiconductor layer 3 formed on a substrate; an active layer 5; a first undoped optical guide layer 6 formed on said active layer; a

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second conductivity type second nitride-based semiconductor layer 7, having a single layer structure formed on said first undoped optical guide layer.

Therefore, in view of Kamimura's teachings, one having an ordinary skill in the art at the time the invention was made would be motivated to modify Ito by incorporating an undoped optical guide layer. The motivation would be to prevent diffusion of dopants into the active layer. Therefore, it would have been obvious to combine Ito and Kamimura so as to yield the device of claim 27.

Re claim 28, Kamimura discloses the band gap of said undoped contact layer (metal) being smaller than the band gap of said second nitride-based semiconductor layer (GaN).

Any inquiry concerning this communication or earlier communications from the examiner should be directed to A. Sefer whose telephone number is (571) 272-1921.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Sue Purvis can be reached on (571) 272-1236.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only.

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ANS November 16, 2007

<u>|A. Sefer/</u>
Patent Examiner
Art Unit 2826